OVERVIEW OF DEVICE SEE SUSCEPTIBILITY FROM HEAVY IONS

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Abstract

A fifth set of heavy ion single event effects (SEE) test data have been collected since the last IEEE publications (1, 2, 3, 4) in December issues for 1985, 1987, 1989 and 1991. Trends in SEE susceptibility (including soft errors and latchup) for state-of-the-art parts are evaluated.

Introduction

Ongoing SEE test programs at JPL ,The Aerospace Corporation, the European Space Agency (ESA), CNES and other organizations are continuing to assess specific part performance for interplanetary and satellite environments and to establish SEE response trends of an ever-increasing body of device data.

In 1985, Nichols et al (Ref. 1) published the first nearly comprehensive listing of SEE test data for 186 parts. This presentation was updated in 1987 (Ref. 2) with the publication of data for 83 additional parts, in 1989 (Ref. 3) with data for 154 parts, and in 1991 (Ref. 4) with data for 182 parts. In this paper, the authors extend the data base for 165 new parts. As before, the data are collected according to technology, function and manufacturer in order to identify trends, generalizations and data gaps.

Testing Approaches

The experimental procedures, such as those used by JPL and The Aerospace Corporation, are evolutionary and are described in detail from time to time in December issues of IEEE Transactions on Nuclear Science (5,6) or in in-house reports. In general, procedures comply with the guidelines for SEE testing set forth by the ASTM F1.11 document (7). They also comply with a JEDEC 13.4 document in preparation, "Test Procedure for the Measurement of Single Event Effects in Semiconductor Devices from Heavy Ion Irradiation."

Organization and Scope of Data

This paper summarizes soft error and latchup experimental test data from the Jet Propulsion Laboratory (JPL), The Aerospace Corporation (A), John Hopkins Applied Physics Laboratory (JH), Centre National D'Etudes Spatiales (CNES, France), European Space Agency (ESA) and other SEE testers. These data are provided directly to JPL or were otherwise made available to the community during the two-year period from January, 1991, through December, 1992. We are pleased to include smaller SEE data sets generated by all U. S. and foreign researchers when these data are made directly available to us. Not included are proprietary data generated by subcontractors who used JPL hardware. Also omitted are now fairly extensive data sets on power transistor burnout obtained by JPL, Rockwell, Boeing and others-- such data require a significantly different organization.

The SEE data presented here and in the previous four reports (1,2,3,4) represent a substantial majority of all test data obtained on SEE throughout the world. Some additional data may exist in other articles of this publication (IEEE-Nuclear Science [Dec. 1993] or this conference's IEEE Workshop Record), in other journals or in published and unpublished presentations of SEE symposia.

The data from all organizations are summarized and collected together even though there are differences in the data from each organization. For example, JPL defines the threshold LET as that value of LET where soft errors are first counted at fluences of 10⁶ ions/cm²; Aerospace now defines their LET threshold as occurring at that point where the measured upset cross section is 0.01 times the measured maximum cross section, CNES reports a threshold at 0.1 times the saturated cross section. JPL's definition virtually guarantees no upset below threshold but results in an overestimate of error rate if the cross section is erroneously assumed to be constant at all LETs greater than the threshold LET. Specifying a threshold LET at a fraction of the saturated cross section attempts to approximate the error rate better, but it introduces an arbitrary factor (to account for the slope of the cross section vs. LET) and an assumption that the saturated value is known and/or achieved with the highest LET test ions.

The best way to calculate error rates is to use the full curve of cross section vs. LET, which may be available from the parent test organization^[1], and integrate it over all angles and all ions of various LETs. But even this method, which involves the use of a computer, relies critically on what assumptions are made about grazing ion impacts and the dimensions of the device cell's sensitive volume.

All data are presently divided into two tables. Table 1 has been revised to include all SEE (soft error) data for both MOS/CMOS and bipolar devices. Table 2 exhibits data for "Latchup Tests Only". All data listed here represent a substantial abbreviation and ignore statistical features altogether. LET limits are for nominal effective values without correction for degradation that can occur when an ion traverses device overlayers. Gold data, in particular, are seldom as damaging as one would expect on the basis of nominal LET and such data are labeled when known, and Au testing is usually not recommended. SEE tests use a dynamic nominal bias (often 4.5 or 5.0 V); latchup tests are usually performed at the maximum value of the nominal bias range (e.g. 5.5V) -- a condition usually (but not always) enhancing the possibility of latchup. Reported data were taken at room temperature or ambient

^[1] JPL data, including more recent results, maybe accessed directly from JPL's computer data base, RADATA.

temperature; higher test temperature measurements may exist for some parts. In some instances, data on transients is noted, which may or may or may not impact electronics down the line. Hence, a system designer interested in a specific part is again urged to contact the appropriate test organization for further information.

Users are cautioned that manufacturers (Appendix I defines manufacturer abbreviations) may often change their process, and resultant SEE susceptibility, without changing the part number or notifying tester organizations. Hence, a test of flight parts is always a good policy.

Trends & Limitations

Trends and device comparisons in the recent data are offered in the "Remarks" column of Tables 1 and 2 and in the following section. However, the organized tabular format is designed to facilitate comparisons. Special studies (such as variation of SEE response with temperature) or a comparison between high energy (GANIL) heavy ion data and that from the lower energy Berkeley 88-inch cyclotron and BNL Van de Graaff are beyond the scope of this presentation. In addition, test data for the whole class of catastrophic failures of power transistors, both MOSFET and bipolar, has recently been organized by Nichols under a substantially different format.

Some colleagues have commented that a measure of the shape of the cross sections vs. LET might be useful-- such as given by a tabulation of the Weibull parameters. Others point out that it may be more difficult to assure that such parameters are properly derived and applied than it is to calculate SEE rates directly from known (and readily available) experimental cross sections.

Program managers concerned with critical system reliability issues will ultimately need an appropriate set of cross sectional data to assess statistical features and focus on specific answers. Ballpark estimates will also have a place, however, by helping assure that expensive experiments are limited to only critical SEE issues.

An Evaluation of SEE Data

Microprocessors

JPL tested a large body of SEE data for microprocessors this year, mostly with 16-bit and 32-bit capability. Soft error thresholds are consistently low for all high-capability machines, with LET(th) ranging from approximately 1 to 10 MeV/(mg/cm²). Important exceptions are two 16-bit devices by Marconi (GEC-Plessey), using their well-established SEE-resistant SOS technology. Most microprocessors are not very susceptible to latchup although there are exceptions (e.g. the IDT R3000 and R3000A.) The Intel CHMOSIV technology is marginally susceptible to latchup, whereas its earlier CHMOSIII technology was not. There is a very large set of data from ESA and Harris on the R3000 and R3000A RISC developed by many manufacturers.

Questions raised last year regarding the best approach to microprocessor testing remain open. The purists argue that static testing of known registers in a known state is the best approach to understanding SEE effects. JPL presently pursues this view and has demonstrated that not all elements of a microprocessor are equally SEE-susceptible, The pragmatists claim that testing with dynamic programs (the more the better) will usually show that static tests provide an unrealistic worst

case.

Some data taken by Europeans groups at GANIL, the higher-energy (1 O to 100 MeV/amu) cyclotron in France, are available. The results suggest that these ions, which are more representative of interplanetary cosmic rays, are more damaging than the familiar lower-energy (2 MeV/amu) ions provided by Brookhaven's Van de Graaff and Berkeley's 88-inch cyclotron. Direct comparisons between energy regimes are few.

It will also be observed in Table 1 that there are data for several controllers and processors of various types. They have similarly low soft error thresholds [< 10 MeV/(mg/cm²)] and varying latchup susceptibility.

Analog-to-Digital Converters (ADCs)

There are several data sets for ADCS and data for two digital-to-analog converters (DACs). Much of the data were taken by JPL in a quest for the least SEE-susceptible 12-bit ADC. The MAXIM devices were clear standouts in this subcategory, but one observes that a completely hard ADC or DAC is a rarity. This is one device type where knowledge of how the device ties in with the system is an all-important consideration in assessing its ultimate suitability.

Static RAMs (SRAMs)

There is much new data to add to the accumulation for SRAMS--with device sizes up to 4 Mbits. All devices employ variations of CMOS technology this test period, and SOI and SOS offer markedly superior resistance to soft errors and latchup. Epi technology (where the epi layer is less than ~10 microns thick) is a good guarantee against latchup but offers no significant advantages against soft errors. A tendency toward stuck bits was observed in the 0.5 micron feature-size Hitachi 4 M SRAM.

Other RAMS

ESA tested a large set of 4M DRAMs and observed a consistent very low soft error threshold typical of this device function. Some non-volatile RAMs were tested—with two Ferroelectric RAMs (FRAMs) for the first time. Some bipolar and CMOS PROMS exhibited relatively high SEU thresholds, but one should note that PROMS are occasionally susceptible to latchup.

Gate Arrays & Bus Controllers

Several gate arrays, configured in different ways, were tested. It is difficult to sort out the large variability in soft error threshold-- even among devices made by the same manufacturer. It is encouraging that no cases of latchup were reported.

Latchup Data

Tests for latchup only are much easier to set up than those designed to measure soft errors as well. Such data are given separately in Table 2-- primarily for devices with different variations of CMOS technology. It has so far held true that

bipolar devices will not latchup with heavy ions. However, latchup has occurred in bipolar devices when exposed to high intensity gamma pulses, and the requisite pnpn parasitic structure exists.

The LET thresholds listed in Table 2 are for latchup only, and cross section data is rarer because of the difficulty in obtaining repeat measurements where catastrophic burnout and overheating may occur. Also presented are data for GANIL which appears to have a devastating effect --including latchup in several devices with epi technology. Once again a need to compare data on identical parts for both high energy GANIL ions and lower-energy ions is manifest.

JPL was able to employ Cf-252 usefully for the first time-- as a screen to reject some ADCS because of latchup. It is cautioned, however, that Cf-252 can never be used to pass a part for latchup because of the possibility that the fission ions do not have adequate range to maintain an adequate LET while generating a funnel at the well-substrate junction.

Latchup observed by MIT-Lincoln Lab in the NSC driver/receivers 26C31 & 26C32, a pair of linear devices, is explained by Sferrino [9]. He notes that the chips have tri-stated digital outputs, comprising an npn and pnp transistor in series-- the familiar structure for latchup paths. This result suggests that other transistor arrangements, such as silicon-controlled-rectifiers, may be susceptible to latchup.

Conclusions

The new data presented here can be combined with data given in References (1, 2, 3 and 4) to develop certain generalizations useful for protecting flight electronics from SEE. Hard technologies and unacceptably soft technologies can be flagged. In some instances, specific tested parts can be taken as candidates for key functions-such as microprocessing or memory. As always with radiation test data, specific test data for qualified flight parts is recommended for critical applications. Calculations of accurate SEE rates will require the assistance of a computer code, a well-defined environment [in terms of flux vs. LET] and a complete device characterization [cross section vs. LET at the appropriate temperature.] Evaluation of catastrophic effects requires its own statistical treatment, in which flares are considered. The recent concern of JPL and others with power transistor burnout and single event gate rupture is beyond the scope of this compendium.

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Appendix I-- Manufacturer Abbreviations

ACT Actel Corp. ADA Advanced Analog Analog Devices Inc. ADI ALS Allied Signal Alters Corp. ALT AMD Advanced Microdevices Corp. ATM Atmel American Tel & Tel ATT BUB Burr-Brown Research CRY Crystal Semiconductor Inc. CYP Cypress Corp. DAT Datel DDC DDC ILC Data Device Corp. EDI EDI Corp. FER Ferranti FUJ Fuiitsu Ltd. GEC GE HAR Harris Corp., Semiconductor Div. HIT Hitachi Ltd. Honeywell Inc. HON IBM IBM I DT Integrated Device Technologies, Inc. INM INMOS Corporation Intel Corp. INT Logic Devices Inc. LDI Linear Technology Corp. LTC LSI LSI Logic Corp. MED Marconi Electronic Devices MCN Micron Technologies MIT Mitsubishi MMI Monolithic Memories Inc. MOT Motorola Semiconductor Products Inc. MPS Micro Power System MTA Matra Harris Semiconductor MXM MAXIM Natel Engineering NAT NEC Nippon Electric Corp. NSC National Semiconductor Corp. owl Omni-Wave, Inc. Performance Semiconductor Corp. PFS Plessey Semiconductors PLS PMI Precision Monolithic, Inc. RAY Raytheon Co., Semiconductor Divison RCA Radio Corporation of America

RTN

SEI

Ramtron SAM Samsung

Seiko

SEQ SEEQ Technology Inc.

SGN Signetics Corp. SIE Siemens Inc.

SIL Siliconix SIP Sipex

SLG Silicon General

SNL Sandia National Laboratories

SNY Sony Corp. SOR SOREP

TEL Teledyne Crystalonics TIX Texas Instruments Inc.

TMS Thomson Military & Space, France

TOS Toshiba TRW TRW Inc.

UTM United Technologies Microelectronics Center

WAF WAF., given in Dufour, 921EEE Workshop Record, Table 1, p25.

XIC Xicor Inc.
XIL Xilinx Corp.
ZOR Zoran
ZYR Zyrel

Appendix II-- Test Organizations

Α	The Aerospace Corporation; El Segundo, CA
RDC	Roeing Physical Sciences Research Center S

BPS Boeing Physical Sciences Research Center, Seattle

CLM Clemson University; Clemson, SC

CNES Centre National d'Études Spatiales; Toulouse, France

ESA European Space Agency-- several facilities

GD General Dynamics

GDD NASA Goddard Space Flight Center; Greenbelt, MD

GE GETSCO, Philadelphia HAR Harris Semiconductor

HON Honeywell

J Jet Propulsion Laboratory (JPL); Pasadena, CA

JH John Hopkins Applied Physics Laboratory; Laurel, MD

LIN Lincoln Laboratories, M. 1. T.; Cambridge, MA

MMS Matra Marconi Space; Vélizy, France

NASA NASA

NRL Naval Research Laboratories, Washington D. C.

R Rockwell International (Anaheim, CA)

SSS S-Cubed

TRW Space and Defense Sector (Los Angeles, CA)

Appendix III-- Test Facilities

88-in. = 88-inch cyclotron, Lawrence Berkeley Laboratory

BNL= Tandem Van de Graaff, Brookhaven National Laboratory, Long Island, NY Cf-252 = A Cf-252 fission source

ESA= European Space Agency -- several sites

GANIL= Cyclotron for Heavy Ions; Caen, France HAR= Van de Graaff at Harwell, England IPN= Tandem Van de Graaff, Institut de Physique Nucleaire; Orsay, France UW= Tandem Van de Graaff, University of Washington, Seattle

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Reference herein to any specific commercial product, process, or service by trade name, trademark, manufacturer, or otherwise, does not constitute or imply its endorsement by the United States Government or the Jet Propulsion Laboratory, California Institute of Technology.

Table 1. SEU DATA-- 1991-1992 (MOS & Bipolar Devices)

Test Org.	Device Fu	nction	Technology	Mfr.'	Bits	Effective LET** Threshold	Cross Section	Section	Facility	Remarks
J	80 C85RH	l MicroP 8-bit	CMOS/epi	HAR	95 tested			65@ LET=60	BNL	7/91. No LU>120. See also J: 6/87.
J	81 C55RI	H Perip to 8085	heral CMO	S/epi	HAR	~2K 40	4E-3(1] 200	88-in	9/91 . [1] RAM data at high LET.
C N	ES SBP99	989 Micr 16-bit	roP Bipolar(I	² L) T	1X	8	1 E-	2	GANIL	11/90. Chapuis.
ESA	80C86-	2/B Mi c 16-bit	roP CMOS/	ері	INT	~1		1000 @ LET=9	GANIL	Harboe-Sorensen IEEE NS 7/92
ESA	80C86 M	licroP C 16-bit	MOS/epi H Mask 1860			1		2000 @ LET = 9	GANIL	Harboe-Sorensen IEEE NS 7/92
ESA	80C86 M	licroP C 16-bit	MOS/epi H Mask 3584			~1		3000 @LET=9	GANIL	Harboe-Sorensen IEEE. NS 7/92
ESA	80C86 N	licroP C 16-bit	MOS/epi F Masks 186							Tandem Van de G. an preceding data.
J	M80C186	MicroP 16-bit	CHMOS II	I INT	-600	9 <u>±</u> 3		250[1]; 450[2] LET= 61]	BNL 9	9/92 [1]=AX,BP, ES [2] = Relocation, SPR,DPR,TCR
GE	80C186	MicroP 16-bit	CHMOSIII	INT	510 d 752	of 4	20)[LET=13]	BNL	6/92. No LU with Au @ 42° angle See preceding.
Α	MG80C186	MicroP 16-bit	CMOS	INT		12	1 E-	3	88-in	No LU>IOO. 10/91
Α	MD8251 O	UART	CMOS	INT		~10		4000	88-in	No LU>I 00. 7/91
JH	1750A	MicroP 16-bit	CMOS/SOS 3-chips	PFS	all 3 chips		3E-4 [@LET	MMU 5 =80]	BNL	92IEEE Workshop J. Kinnison (7/92)
J	MA31 750	MicroP 16-bit	CMOS/SOS	S MED)[1]	175 No	upset 1	No upset	BNL	6192. LU>l 75. [1] GEC-Plessey
ESA	MAS281	MicroP 16-bit	CMOS/SO	S ME	D	>60 No	upset	No upset	GANIL	Consistent with JPL data of 5/89 2.5 μm.

* See listing of abbreviations in Appendix 1.

[&]quot; LET is Linear Energy Transfer= the density of ionization along an ion's path in MeV/(mg/cm²). The cosine law for beam angle is applied where valid to obtain "effective" LET.

See listing of abbreviations in Appendix III.

See listing of abbreviations in Appendix II.

^{*&#}x27;* Unless otherwise noted, the cross section (upsets/f luence per device) is given for 240-380 MeV Kr or Brat normal incidence, having an LET=36 to 40 MeV/(mg/cm²).

JH RTX201 OF	RH MicroP TSOS-4 HAR 16-bit process	15	50(Au)		BNL	No LU. 921EEE Workshop (7/92)
J 80386	MicroP CMOS AMD 32-bit	>>	·2.5	•-•	BNL	7/91 LU(th)<<24.
J 80386	MicroP CHMOSIV INT 32-bit	272 3.5	5 <u>+</u> 1	100	BNL	5 & 7/91.LU=40.
GDD 80386	MicroP CHMOSIV INT 32-bit				BNL	7/92. LU=27. 7E-5 cm ² .
CNES 68020	MicroP CMOS/epi MOT 32-bit	varies <1.	.7 1E-2 ^[1]		IPN !	92IEEE Workshop 1 =register test
CNES 68020	MicroP CMOS/bulk MO 32-bit	T varies <1	.7 1E-2 ^[1]		IPN :	92IEEE Workshop 1 =register test
HAR R3000	MicroP Adv. CMOS PF 32-bit	S -1300 <3	3.4 1 E-3		BNL D. V	5/91 . No LU>120. ail (HAR). Table 2. VLSI MIPS RISC.
HAR R3000	MicroP Adv. CMOS S 32-bit	IE -1300 6	6 1 E-3		BNL	5/91. No LU>120. D. Vail (HAR). Table 2. VLSI MIPS RISC.
ESA R3000	MicroP CEMOS IV IDT 32-bit	736 (23 reg.)			BNL	LU(th)<3.3. RISC Harboe-Sorensen 921EEE Workshop
ESA R3000	MicroP CMOS LSI 32-bit	736 ^ (23 reg.)	~3	300	BNL	No LU>60. RISC Harboe-Sorensen 92IEEE Workshop
ESA R3000	MicroP PACE I PFS 32-bit	736 ~ (23 reg.)		100	BNL	No LU>60. RISC Harboe-Sorenseri 92IEEE Workshop
ESA R3000	MicroP Adv. CMOS SIE 32-bit	736 < (23 reg.)	<10 	100	BNL	No LU>60. RISC Harboe-Sorensen 92l EEE Workshop
ESA R3000	MicroP CMOS NEC 32-bit	736 (23 reg.)	<lo< td=""><td>120</td><td>BNL</td><td>LU(th)=60. RISC Harboe-Sorensen 92IEEE Workshop</td></lo<>	120	BNL	LU(th)=60. RISC Harboe-Sorensen 92IEEE Workshop
ESA R3000A	A MicroP CEMOS V IDT 32-bit	736 ^ (23 reg.)	~6	>100	BNL	LU(th) =27. RISC Harboe-Sorensen 921EEE Workshop
ESA R3000A	A MicroPHCMOS LSI 32-bit	736 < (23 reg.)	<8 	100	BNL	LU(th)= 60. RISC Harboe-Sorensen 92I EEE Workshop
ESA R3000A	MicroP PACE II PFS 32-bit	736 < (23 reg.)	6	120	BNL	No LU>60. RISC Harboe-Sorensen 921EEE Workshop
ESA R3000A	MicroP Adv. CMOS SIE 32-bit	736 ~ (23 reg.)	6	200	BNL	No LU>60. RISC Harboe-Sorensen 921EEE Workshop

CNES L64730 DCT Proc. CMOS	LSI	8 2E-3	GANII	921EEE Workshop Dufour, 7192 '
BPS 87C51 FB/ MicroC CHMOS 87C51FC 8-bit	III INT -2300 tot al	~3[1% sat]	400[1] 88-in	8/92 This is non- hard version of 80C51. Oberg. [1] = IRAM/DRAM LU=10;1 E-3 cm².
GDD 82380 DMA Cont. CHMO 32-bit	SIII INT 900 <	<11 >1 E-4	BNL	IEEE92 Workshop Record, PI.
ESA R301OA FP Accel. CEM Coprocessor	OS V IDT 102 (32 reg		>100 BNL	No LU>27. Harboe-Sorensen 921EEE Workshop
ESA R301OA FP Accel. HCMOS Coprocessor	LSI 1024 (32 reg		100 BNL	LU(th) = 27. Harboe-Sorensen 92IEEE Workshop
ESA R301 OA FP Accel Coprocessor	PFS 1024 (32 reg		>40 BNL	No LU>27. Harboe-Sorensen 921 EEE Workshop
ESA R301oA FP A ccel. Adv. (Coprocessor	CMOS SIE 10 (32 reg		200 BNL	No LU>60. Harboe-Sorensen 921 EEE Workshop
GE 80387-16 Coprocessor CHM0	OSIV INT all 64	0 4 20[LET=24] BNL	10/92. See Table 2. LU(th)=24 to 37.
CNES 68882 FP Coproc. CMOS/ 32-bit	epi MOT varie	s 3 1E-2[1] IPN	921EEE Workshop 1 =register test
CNES 68882 FP Coproc. CMOS 32-bit	MOT varie	s 3 1E-2 [[]	1] IPN	921EEE Workshop 1 =register test
MMS TMS320C25 DSP CMOS	TIX(Fr?) [Ref. [Ref.		GANIL	Dufour, 92IEEE Workhop. (1)=MPY test program; (2) = RAM test. LU=31; 1E-4 cm².
JH ADSP2100A DSP CMOS/ep commerci	oi ADI al	13 5E-3	BNL	LU ≈13.5 ; 1 E-4cm²
JH also reports that an experimental (See J. Kinnison, IEEE NS Dec 91, p			ifferent substrate	, exists with: No LU>120.
NRL ADSP2100A DSP CMOS/α 13 μm	epi ADI	7 3E-4	BNL	No LU>>38, but a 17 μm epi std.

ESA ADSP21 00A DSP CMOS/epi ADI 531 12.5 µm

production part latched up easily.

300

IPN

M. DeLaus-- 1/91

 $LU=12; 2E-5 \text{ cm}^2.$

Harboe-Sorensen IEEE NS Dec 92, p441. See above.

J HSRDI056 Resolver Hybrid Dig. Conv. RHCMOS		tested <1	3 5E-5	E	NL 12/91. No LU >110.
SSS DAC8408 8-bit DAC CMOS	PMI	- 45	4E-5	B	NL 1/92, No LU>89.
BPS AD558 8-bit DAC Bipolar(I ² I	_) ADI	<<	5 >2E-4	L	w 2/92.
HON PM7545 12-bit DAC	PMI	- 24	1.4 E-4	B	NL 10/92. DC: 9142 No LU>>37. WP-02
A DAC8412 12-bit DAC BICMOS	PM I	25	2E-4	88	in No LU>100. 10192
HON AD9048TQ 8-bit ADC [1] Flash	ADI	· <<	3 3.2 E-4	B	NL LU=7;1.3 E-5 cm². [1]= bipolar, but LU raises questions of possible CMOS also. DC:9142 & 9222 WP-02. 10/92
A MP7684 8-bit ADC CMOS Flash	MPS	- ~1	1 E-3	88	-in 12/91. See Table 2: J: No LU>120. 11/92
BPS AD7824 8-bit ADC CMOS	ADI	- <<	5 >1E-4[L	ET=10] UV	V 2/91. Fl ion only.
J AD7672B 12-bit ADC CMOS	ADI	62	2E-4[8 MSB's]	BNL 88	& 7 & 9/91. No LU in >175. See Table 2.
J MX7672 12-bit ADC BICMOS	MXM	20	>2E-4	B	NL 11/92
J MX7572 12-bit ADC Bipolar/ CMOS?	MXM	- 20	>2E-4	B	NL 11 /92
HON HI574 12-bit ADC CMOS	HAR	- 10	8E-5	B	NL No LU>>37. 10/92 DC: 9210
J HI674ALD 12-bit ADC DC9205	HAR	6	>1E-4	B	NL 11/92 See below. No LU>120 at 80° C. Earlier DC is latchable.
J HI674ASD 12-bit ADC DC9028	HAR	- 6	•	E	NL 11/92 LU(th)=30. See above.
J AD574A 12-bit ADC BiMOS	ADI	<3	T PP	8	8-in 9/91. No LU>110.
J AD674A 12-bit ADC Bipolar (Two chip)	ADI	- <3		8	8-in 9/91. No LU>I 10.
J AD674B 12-bit ADC BiMOS	ADI	<3	>5E-4	B	NL 11/92. No LU>120.
J MX674A 12-bit ADC BiCMOS	MXM	~3	>1 E-3	E	NL 11/92. No LU>120.
J ADC574A 12-bit ADC Bipolar/ CMOS	BUB	- <<	40	E	NL 7/91. LU LET<< 40.
J ADC674 12-bit ADC Bipolar/ CMOS	BUB	- <<	40	B	NL 7/91. LU LET<<40.
J AD7872 14-bit ADC BiCMOS	ADI	<1.	.4 1 E-3	B	NL 9/92, NoLU>104
A HS9576RH 16-bit ADC CMOS Hybrid	SIP	3	5E-4	88	3-in No LU>100. 1/92

JH	54AC708	3 FIFC	CMOS/epi	NSC	64x9	21	8E-4		BNL	92IEEE Workshop Kinnison
JH	74AC72	5 FIFC	CMOS/epi	NSC	512x9	9	3E-3		BNL	921EEE Workshop Kinnison. "Minilatch"
GDD ·	7202RE	FIFO (10 μm)	CMOS/epi I	DT 1	Kx9	3.5	4.2 E-3	46	BNL	LU=38.9192. G Compare Table 2
CLM I	HC5517A	SRAM	CMOS	TIX		5 @	5E-6 LET=24		BNL	McNulty- IEEE '91
A L	_6116	SRAM	CMOS/ NMOS	LDI	2Kx8	5	8E-3	50	88-in	LU =15;1 E-3cm². 12192
A C	YPC128A	SRAM	CMOS/ NMOS	CYP	2Kx8	2	7E-3	40	88-in	LU =10;1E-4 cm ² . 12/92
HON	HC6116	SRAM	CMOS[1]	HON	2Kx8	14		100	BNL	IEEE NS 6/92 p450 [1]= with variable R.
HON	HC6216	SRAM	CMOS[1]	HON	2Kx8	25 to 40)	80	BNL	IEEE NS 6/92 p450 [1]= with variable R.
J I	HX6364	SRAM	CMOS/SOI DC9029	HON	8Kx8	>90			BNL	5/91 . No LU>90 up to 125 deg C.
HON	HC6364	SRAN	M CMOS/ep	і НОМ	I 8Kx8	56			BNL	DC=? See above.
HAR	TS054	SRAM	Std Cell [1]	HAR	64K	>138			BNL	No LU. W. Newman 10/91. [1]=Rad Hard CMOS/SOS.
ESA M	MA6167 S	RAM C	MOS/SOS N	/IED 1	6Kx1	-40	@	2 LET=75	88-in	3,0 μm technology
ESA	MA6116	SRAM	CMOS/SOS	MED	2Kx8	30	 @	5 LET=75	88-in	3.0 μm technology
ESA I	MA9187 S	SRAM C	MOS/SOS	MED (64Kx1	~60	 @	2 LET=120	88-in	1.5 μm technology
J i	BM6401 S	RAM C	MOS/epi IBN	л 64K)	x1 >115	No up	set No	upset	BNL	6/92. Development SRAM, No LU>I 15.
ESA	EDH88320	SRAM	1 NMOS/CM	OS ED) 32Kx8	3~2		100		I/91. No LU reported IEEE 91. Compare '87 Aerospace data .
A N	MT5C256	SRA	M CMOS/ NMOS	MCN	1 256K	x1 ~3	-1[1]		88-in	[1]= Factor of 100 lower for high R. No LU>100, 6/92
A M	AT5C2568	SRA	M CMOS/ep	oi MCI	N 32Kx	8 3	0.9		88-in	No LU>I 00. 7/91
MMS	MT5C2568	3C SRAI	M CMOS 2M-2P	MCN	I 32Kx8	<1	0.6	(LU(th)=23; 1 E-2 cm ² Dufour, 921EEE Workshop 7/92 Multiple upsets

CNES MT5CIO01 SRAM CMOS MCN 1 Mx1	4.5	0.5		IPN Date Code 9133
CNES MT5C1 008 SRAM CMOS/epi MCN 128Kx8	~2	0.6[1]		IPN <5/91. DC8116 No LU>26. Possible multiple errors/strike. (1)= Worst case all 1's
CNES MT5C1OO8 SRAM CMOS MCN 128Kx8	6[1]	1.8		IPN Date Code 9125. [1]= at 10 % of sat. See Table 2.
CNES MT5CI 008 SRAM CMOS/epi MCN 128Kx8	5[2]	2.0 (1)		IPN Date Code 9101 (1)=Worst case all 1's [2]₌ at 10 % of sat.
CNES MT5C1OO8 SRAM CMOS(I) MCN 128Kx8	<7 ^[2]	2E-3		IPN (1) = low current resistor process. [2]= at 10 0/° of sat.
A MT5C1 008 SRAM CMOS/epi MCN 128Kx8 NMOS	4	2	•••	88-in IEEE91, No LU>100. Multiple errors/strike. A high resistivity DUT: SEU cross=~1E-2 cm2.
J MT5C1OO8C SRAM CMOS/epi MCN 128Kx8 [new version]	<3	2E-2		88-in 9/91. No LU>I 10. No date code.
CNES HMS65641 SRAM CMOS/epi MTA 8Kx8 [12 μm]	2.5 10[1]	0.2	300	IPN 8/91. LU=50;4E-4 cm2. [1) = at 10 % of sat, Compare earlier CNES data.
CNES HM65656 SRAM SCMOS MTA 32Kx8 6[10% sat	1] 0.1		IPN 1992. Engr. sample
CNES HM65664 SRAM SCMOS MTA 8Kx8 911 Final process	I O% sat	t] 0.4		IPN 9/91. No LU>50. R. Ecoffet
NASA HM1 -65664 SRAM SCMOS/epi MTA 8Kx8	3 5		30	BNL; 12/90. 1 μm.; GANIL/IPN No LU at LET=116
CNES HM65641 SRAM CMOS/epi MTA 8Kx8	10	0.2		IPN Date Code 8933
CNES TS4H6408 SRAM SOI TMS 8Kx8	>114			IPN Date Code 9151
A IDT7052 SRAM CMOS(V)/ IDT 2Kx8 NMOS	4	8E-2		88-in No LU>100. 10/92
A IDT7164 S R A M CMOS(V)/ IDT 8Kx8 NMOS '	3	0.1	 -	88-in LU=8;8E-3 cm ² . 10/92
A MCM6226 SRAM CMOS/ MOT 128Kx8 NMOS	3 <3	0.2	***	88-in LU=45;2E-5 cm². 10/92
A CXK581000P-10L SRAM CMOS/ SNY 128KX NMOS	(8 3	8E-2		88-in LU=55;2E-5 cm². 2/90 (Corrected)\
A CXK581 001 SRAM CMOS/ SNY 128Kx NMOS	8 3	0.15	*	88-in LU=30;5E-5 cm². 10192
GDD HM628512 SRAM Hi-CMOS/epi HIT 512Kx 0.5 μm feature	8 ~1.5	1.25	30	BNL 9/92. No LU>90 Stuck bits seen.

R	EDI 41024 C100QB DRAM	ED	DI IMx1	1.4	0.11	10	BNL No LU>82. 4192
R	Mosaic MDM1 100TMB DRAM		NEC II	Mx1 <0.	5 0.24 2	24	BNL LU(th)=25; 1 E-4 cm ² dynamic test. 4/92
R	Mosaic MDM1400G DRAM	- HIT	4Mx1	~2		12	BNL No LU>82. 4/92
ESA	MBB14IOO-1OPSZ DRAM CMO	S FUJ	4Mx1	~1		80	IPN No LU>50RADECS91
ESA	HM514100ZP8 DRAM CMOS H	IT ·	4Mx1	~2		12	IPN No LU>40 RADECS91
ESA	MT4C1 004C DRAM CMOS[1]	MCN 4	4Mx1	~2		30	IPN No LU>40 RADECS91 [1]=Engr. sample. See also Table 2 & below.
Α	MT4C4001 DRAM CMOS/epi 7 micron	MCN	1Mx4	~3 ~	2 (4.5V)		88-in No LU>I 00. 3/92
ESA	D424100V-80 DRAM CMOS N	NEC 4	4MxI	~1		40	IPN No LU>50RADECS91
ESA	KM41 C4000Z-8 DRAM CMOS	SAM	4MxI	~2		40	IPN No LU>40 RADECS91
ESA	HYB514IOOJ-10 DRAM CMOS S	IE -	4Mx1	~1		60	IPN No LU>40 RADECS91
ESA	TMS44100DM-80 DRAM CMOS [EPIC]	TMS	4MxI	~1		40	IPN No LU>40 RADECS91
ESA	TC514100Z-10 DRAM CMOS TO	os ·	4MxI	~1		60	IPN No LU>40 RADECS91
CNE	ES P10C68 RAM CMOS/ PL Non-vol. SNOS	S	8kx8	7(1)	0.35 ⁽¹)		IPN (1) = SRAM config.
CNE	S PI oC68 RAM CMOS/ PL Non-vol. SNOS	S	8kx8	>114 ⁽¹⁾			IPN (1)= EEPROM configuration.
J	FMx1408 FRAM CMOS R	TN 2	2Kx8	<<30	2E-4(dy	n.)	Cf-252 6/92. LU LET<<30
J	FMx1208 FRAM CMOS/epi R	RTN	512x8	~11	3E-3[dy	n.]	BNL 6192. LU LET=45.

CNES 28 HC256 EEPROM CMOS/FG SEQ 32kx8 >54	IPN Date Code 9025
CNES 28 HC256 EEPROM CMOS/FG ATM 32kx8 >54	IPN Date Code 9032
CNES X28C256 EEPROM CMOS/FG XIC 32kx8	IPN DC 9032. Table 2
A DM28C256 EEPROM CMOS/epi SEQ 32kx8~15* 1 E-4* 5** 4E-4**	88-in No LU>I 00. 5/91 *= READ. **=WRITE Compare following.
GDD 28C256 EEPROM CMOS/epi SEQ 32kx83.4(write) 5E-3	BNL Perm. fail@ LET=60 IEEE92 Workshop pl
MMS CY7C261-55 EEPROM CMOS/FG CYP 8kx8 <32 0.2	GANIL 921EEE Workshop Dufour 7/92
MMS WSF57C49B EEPROM CMOS/FG WAF 8kx8 45 5E-2	GANIL 92IEEE Workshop Dufour 7/92 LU(th)<32; 3E-4 cm².

MMS HM6617 PROM CMOS	HAR 2kx8 32	3E-4	GANIL LU=58; 2E-4 cm². 92 IEEE Workshop Dufour.7/92. Compare earlier data.
MMS R29793DM PROM Bipolar	RAY 8kx8 8 (peri	3E-5 pherals only)	GANIL No LU>87.Dufour, 921EEE Workshop
GDD 82 HS641A PROM Bipolar	SGN 8kx8 >73		BNL No LU>73,7/92. Compare to next.
MMS 82 HS641 PROM Bipolar	SGN 8kx8 31	7E-6	GANIL No LU>120 7192 Compare above.
J UT1553 Bus Controller CM OS/ep	oi UTM 164/732 60		BNL 5/91. No LU>120.
MMS TC02 MACS Bus Cont. MA G	6A MTA 110	>3E-6	GANIL No LU>124. Dufour 92IEEE Workshop
GDD Bus Cont. ASIC(Bus) CMOS	S/epi MTA 8	1.5 E-5	BNL No LU>87. 7192 FSC design
GDD Serial Cont. ASIC(Bus) CMC	OS/epi MTA 4.5	>4E-5	BNL No LU>87. 7/92 FSC design
CNES ULA 5N104ASIC(Bus) Bipola	ar FER <5.5	2E-3	GANIL Chapuis, ESA Conf.1 1/90 No LU>88.
MMS MC5000 Gate Array C M (Memory Plan.)	OS MTA 30	5E-3	GANIL No LU>62.Dufour 92IEEE Workshop See JPL data "87.
HON HR1 060 Gate Array RICMOS	SIII HON Multicell 22		00[1] 88-in 7/91 [1]=D flip-flop 0[2] [2]= RAM config.
GDD XC3090 FPGA CMOS	XIL		BNL LU(th)=5; 5E-3 cm2 DC9110 & 9045. 7/92
A A1280 FP GA CMOS/epi (1.2 μm featu	ACT 1200 30[1] re) 5[2]	300 800	D[1] 88-in 1991, ACT II family 0[2] [1]=C module [~10 PLD-equivalent gates.] [2]=S module. No LU>120. See Ref. 8
A LRH1 0038Q PPGA[I] CMOS, rad-hard (1.5 µm fe	gates	10	88-in See Ref 8. [1]= Process Prog. G A No LU>120.
A HPo3 PPGA CMOS/epi rad hard (1.5 μm fea	i UTM Test 45 Chip ature)	10	88-in See Ref. 8 No LU>80.
A RA20K PPGA CMOS/ep rad hard (1.0 μm fea	Chip	10	0 88-in See Ref. 8 No LU>I 20. 3/92 D F/F's; SRAM
ESA EP31 o Prog. Logic Dev	ALT 5.4	3.6 E-6(sat)	HAR[1] 6/91 [1]= Van de G.

ESA EP600 PLD	ALT	8	3E-6(sat)	HAR[1] 6/91 [I]= Van de G.
ESA 20RA10Z PLD	SEQ		4.2 E-5	Cf-252 6/91. Latchup.
GDD 22VI OC-1 O PAL BICMOS	CYP	>120		BNL No LU>I 20. 12/92
GDD 22V1OD-I5DMB PAL CMOS	S CYP			BNL LU(th)<<26. 12/92
A 22V1OB PAL CMOS	CYP	5		88-in LU(th)=12; 5E-4 12/92
IBM 22VI O PAL CMOS	CYP	5	7E-6	BNL LU(th)=25; 3E-4 cm2 Die similar to below.
IBM 22V1O PAL CMOS	MMI	5	1 E-5	BNL LU(th)=25; 3E-4 cm2 Die similar to above.
A 22V1 OA PAL Bipolar	AMD	4	2E-5	88-in 6/92
A 22V1 OA PAL Bipolar	TIX	4	2E-5	88-in 6/92
IBM IDT49C460 EDAC CMOS (32-bit)	IDT	17		BNL LU(th)=25; 2E-3cm2.
A IDT49C460 EDAC CMOS (32-bit)	IDT	>100) <l e-7<="" td=""><td>BNL No LU>100. 5/91 Compare preceding.</td></l>	BNL No LU>100. 5/91 Compare preceding.
IBM EDAC CMOS (32-bit)	AMD	5	1 E-4	BNL LU(th)=25; 5E-4 cm2.
MMS 54LS630 EDAC LSTTL	TIX	7	1 E-3	GANIL No LU>32. Dufour, 921EEE Workshop
MMS 54 LS74A D- FF LSTTL	TIX 4	7	1 E-4 2500	GANIL No LU>32. Dufour, 92 IEEE Workshop
MMS MC10531D- FF bipolar/ ECL	MOT 4	<32	1 E-5 250	GANIL No LU>116. Dufour, 92 IEEE Workshop
A 54LS112 J-K/FF TTL(LS)	MOT 2	6	1 E-4 5000	88-in 6/92
BPS 555 Timer bipolar	NSC	5	>2E-5(LET=1 O)) UW 2/92
BPS 555 Timer bipolar	SGN	5	>2E-5(LET=1 O)) UW 2/92
MMS 54ACTI 63 Counter FAC	Т МОТ	80	6E-6	GANIL No LU>I 40. Dufour, 921 EEE Workshop
MMS 54 ACT374 D FF FACT	MOT	>140		GANIL No LU>140. Dufour, 921EEE Workshop
HON 54ACTQ373 D-Latch	NSC Octal	29	8.6 E-5	BNL No LU>>37.DC8942 WP-02 10/92
A 54 HCT373 Latch CMOS/HC	T TIX Octal	·-70	5E-6	88-in No LU>100. 1/91
A 54 HCT393 Counter CMOS/	HCT HAR/GE	8 23	4E-5	88-in No LU>I 00. 6/92

Table 2. Latchup Test Only (1991-1992)

Test Device F Org.	unction Technology		Bits Effective LET'* Threshold		Facility Remarks **
JH 64500/1	MicroP CMOS/epi (16-bit)	LSI	- 75		BNL 1750A CPU.
LIN 68020	MicroP CMOS/epi (1 6-bit)	MOT	32 <u>+</u> 6		BNL 4/91
A HS82C88	Bus Cont. CMOS	HAR	55	4E-6	88-in 12/91
A HS82C59A	Priority Int. CMOS Controller	HAR	16	2E-3	88-in 12/91
A HS82C52	Ser. Cont. CMOS Interface	HAR	- 50	2E-5	88-in 12/91
HAR R3000	MicroP CMOS? (32-bit)	IDT	- 4.8		BNL May 91. Table 1. MIPS RISC. D. Vail (HAR)
HAR R3000A	MicroP CMOS? (32-bit)	IDT	26		BNL May 91. Table 1. MIPS RISC. D. Vail (HAR)
HAR R3000A	MicroP CMOS? (32-bit)	PFS	60		BNL May 91. Table 1. MIPS RISC. D. Vail. See Table 1
HAR R3000	MicroP CMOS (32-bit)	LSI	53		BNL May 91. Table 1. MIPS RISC. D. Vail.

^{*} See listing of abbreviations in Appendix I.

^{**} LET is Linear Energy Transfer= the density of ionization along an ion's path in MeV/(mg/cm²). The cosine law for beam angle is applied where valid to obtain "effective" LET.

See listing of abbreviations in Appendix III.

See listing of abbreviations in Appendix II.

^{**&#}x27; Unless otherwise noted, the cross section (upsets/f luence per device) is given for 240-380 MeV Kr or Brat normal incidence, having an LET=36 to 40 MeV/(mg/cm²).

	croP CMOS/epi 2-bit)	LSI	16.5	5 4E-3	GANIL SPARC. Dufour, 921EEE Workshop
	croP CMOS 2-bit)	LSI	8.2	5E-2	GANIL SPARC. Dufour, 921EEE Workshop
MMS L64814 F. (3	P. U. CMOS/epi 2-bit)	LSI	10	2E-3	GANIL SPARC. Dufour, 92IEEE Workshop
MMS T800 Transp (3	puter CMOS 2-bit)	INM	45	>1 E-4	GANIL Dufour, 921EEE Workshop
A WE-DSP32C	DSP CMOS	ATT	17	1.7 E-2	88-in June 1992
J 320C25 D	SP CMOS/epi	TIX (France)	36@ ⁻	1 E5 ions/cm ²	BNL LU=26 at 125 deg. C 5/91, DC 8939. Compare to earlier data. See Table 1.
	SP New CMC μm epi	S/epi TIX	80		BNL 921EEE Workshop Kinnison, 7/92. See previous & Table 1.
A 320C30 D	SP CM OS/epi 7pm epi	TIX	13	5E-5	88-in 12/92. Compare to 1EEE91.
J 320C50 D	SP CMOS/epi	TIX	>69		BNL 6/92
LIN 56001 D	SP CMOS	MOT	12		BNL 4/91, Dynamic test. See also Table 1.
JH ADSP2100A DS (1	SP CMOS/epi 6-bit) 18 μm	ADI	13	1 E-4	BNL IEEE NS (Dee 91) p 1398. See below.
MMS ADSP21 00A [1	DSP CMOS/epi 6-bit]	ADI	26 1	E-3	GANIL 92IEEE Workshop Dufour 7192
JH ADSP2100 [1	DSP 6-bit]	HIT	9 <u>+</u> 2		BNL 4/90.
MMS ADSP2100 DS	SP CMOS/epi 6-bit]	ADI	<30	_	GANIL 921EEE Workshop Dufour 7192
J AM29CEPL154 M	MicroC. CMOS	AMD	10	2E-3	BNL 6/92
CNES 68881 Copre	ocessor HCMOS/ 1.5 μm	oulk MOT Custom	6	4E-3	IPN DC 8942. Compare to 68882 below.
CNES 68882 Copro	ocessor HCMOS/t 1.2 μm	oulk MOT Custom	12	1 E-3	IPN DC 9022. Compare to 68881 above.
J 80387 Coprocess	sor CHMOS IV	INT all 640	40	3E-5*(sat)	88-in 9/91. *Deduced from INT 80386Table 1, CHMOS IV (J: 7/91).
GE 80387-16 Cop	roc. CHMOSIV	INT all 640	24 to	37	BNL 10/92. See Table 1.
GDD 80387 Copro	c. CHMOSIV	INT all 640	31	4E-5 (sat)	BNL 7/92

J MP7684/ 8-bit ADC CMOS MP7684A (Flash)	MPS	>120	BNL" 11792 up 10125°C.
CNES TMS8338 8-bit ADC CMOS (HS13)	TMS	~20 5E-4	IPN Aug 91 See following entry.
CNES TMS8338 8-bit ADC CMOS (HCMOS3)	TMS	12 2E-3	IPN Aug 91 See preceding entry.
A MP7695 10-bit ADC CMOS	MPS	>>100	88-in Jun 92
TRW ADC87 12-bit ADC Hybrid? DC: 8920/91 28	BUB [L	? >>3E-5 ET= 60]	BNL 7/92. T. C. Lunn
TRW ADC85 12-bit ADC Hybrid? DC: 9203	SIP	>>60	BNL 7/92. T. C. Lunn
J SP7800 12-bit ADC CMOS	SIP	<<30 <1 E-4	Cf-252 4192
J LTC1 272 12-bit ADC CMOS	LTC	<<30	Cf-252 10/92
J H1774B 12-bit ADC BICMOS	HAR	<<30	Cf-252 10/92 (DC9022) BNL 11/92
LIN ADSI 12 12-bit ADC	DAT	38	BNL 4/91
SSS CS5016 16-bit ADC CMOS	CRY	<<12	BNL 1/92. Compare JH; Aerospace data [5/90].
A CS5016 16-bit ADC CMOS/e	pi CRY	15 5E-3	88-in 5/91. See above.
J AD7533 10-bit DAC CMO	S ADI	>120	BNL 11/92up to 125° C.
J MP7533 10-bit DAC CMOS	MPS	>120	BNL 11/92 up to 125° C.
MMS SOR7541 12-bit DAC CMOS	SOR	>116	GANIL Dufour,92IEEE Workshop
JH 7134RT FIFO CMOS	I DT 8kx8?	15	BNL Kinnison 4/92
JH 7202RT FIFO CMOS	IDT 1kx9?	15	BNL Kinnison 4/92
GDD 7202 RE FIFO CMOS/epi	I DT 1 Kx9	38	BNL See Table 1.
MSS M67202 FIFO SCMOS/epi RT	MTA 1kx9	>140	GANIL 92IEEE Workshop Dufour 7/92
GD CY7C1 85 SRAM CMOS	CYP 8kx8	<<40 8E-5	Cf-252 4/94 SEE Symp. High Temp exists.
CNES HM65641 SRAM CMOS/epi	MTA 8kx8	<55	IPN Chapuis, at ESA Conf. 1 1/90
MMS HM65664 SRAM SCMOS/epi R	T MTA 8kx8	>140	GANIL 921EEE Workshop Dufour 7/92. See Table 1.
MMS HM65656 SRAM SCMOS/epi R	T MTA 32kx8	>140	GANIL 92IEEE Workshop

ESA D4464D SRAM CMOS NEC 64K ~2 0.18	5[LET=12]Harwell IE	EEE '92. Proton LU also occurs.
LIN MT5C1 608 SRAM MCN 27	BNI	_ A pril '91.
LIN MT5C2568 SRAM CMOS/epi MCN 32kx8 >164	BNL	. Sferrino '91
LIN MT5C2568 SRAM CMOS MCN 32kx8 38 to 6	69 BNL	Sferrino '91. Compare above.
MMS MT5C1 008 CW SRAM CMOS/bulk MCN 128kx8 75	4E-4 GANI	L Compare Table 1. 92IEEE Workshop Dufour, 7/92
LIN DPS92256G SRAM CMOS HIT 32kx8 <27	BNL	. Sferrino '91
CNES MT4C1 O04C DRAM CMOS/epi MCN 1 Mx4 >54 0.8 μm epi	IPN	DC 9109
LIN R29793 SROM CMOS/epi? RAY 8kx8 >164 fuse-link	BN	L Sferrino '91
CNES X28C256 EEPROM CMOS/FG XIC 32kx8 18	1 E-3 IPN	Date Code 9032
LIN 28C256 EEPROM CMOS/epi SEQ 32kx8 >164	BNI	Sferrino '91
LIN 28C64 EEPROM CMOS/epi? SEQ 8kx8 >164	BNI	Sferrino '91
MMS MB7144E PROM Bipolar FUJ 8kx8 >104	GANI	L 921EEE Workshop Dufour 7/92
CNES 1020A FPGA CMOS/epi TIX[1] >27	IPN	DC 9109 [1] = 547 logic modules, 4 ports /module, config. antifuse
MMS MC5000 GA 35K SCMOS/epi RT MTA >80	GANI	92IEEE Workshop Dufour 7192
MMS MA805 1553 Bus Cont. CMOS MED <36 -	GANI	921EEE Workshop Dufour 7/92
MMS TMC2210 Mult./Accum. CMOS TRW >61 -	GAN	L 92IEEE Workshop Dufour 7/92
A ATW28XX DC/DC Conv. CMOS ADA 51 to 80 module (one IC)	1E-6 88-i	n 10/91
J 26C31 Driver CMOS/SOS HAR None >120	BNL	9192
LIN 26C31 Driver CMOS NSC None 20	BNL	. Sferrino '91
J 26C32 Receiver CMOS/SOS HAR None >120	BNL	9/92, saturated SEU=3E-5 cm ²
LIN/SSS 26C32 Receiver CMOS NSC None 20	BNL	. LIN: '91; S ³ : '92

A LTC485CN8 Trans	sceiver CMOS	LTC	3	8E-5	88-in	June 1991	
MMS DG271 Analog	Switch CMOS S	SIL Quad	>137		GANIL	92IEEE Workshop Dufour 7/92	
MMS DG300 Analog	Switch CMOS S	SIL Dual	>137		GANIL	921EEE Workshop Dufour 7/92	
A DG601 AK Analog	Switch CM OS 13 micro	-	>100		88-in	3/92	
A IH6208 Analog	MUX CMOS	HAR	>100		88-in	12192	
A LTC1 064 Low Pa	ass Filter CMOS	S LTC	15	3E-4	88-in	12/92	
JH 54ACTQ244 Lo	gic FACT w. I/C	O NSC	>120		BNL	1/91 NSC's FACT DC >8826 are designed LU-proof.	
LIN P54PCT245 Log	gic CMOS	PFS	<27		BNL	4/91	
A 25 HCT04 SA	R CMOS	ZYR	22	3E-4	88-in	7/9 1	